## **AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

## **LISTING OF CLAIMS:**

1. (Original) A multi-foil optic comprising:

a plurality of flat plates each having a reflecting surface, and positioned normal to an arc to provide total external reflection to high energy radiation incident on the plates from a high energy radiation source, to focus the incident high energy radiation on a designated surface, wherein each plate has a thickness in the range of  $50\text{-}70~\mu m$ .

- 2. (Original) The multi-foil optic of claim 1, wherein the high energy radiation comprises X-ray radiation.
- 3. (Original) The multi-foil optic of claim 1, wherein the high energy radiation comprises extreme ultraviolet (EUV) radiation.
- 4. (Original) The multi-foil optic of claim 1, wherein the plates are made of glass.
- 5. (Original) The multi-foil optic of claim 1, wherein the plates are made of mica.

6. (Currently Amended) A method for performing high energy radiation lithography, comprising the steps of:

receiving high energy radiation from a high energy radiation source;

focusing the high energy radiation from the high energy radiation source using a multi-foil optic, the multi-foil optic comprising a plurality of flat plates each having a reflecting surface, and positioned normal to an arc to provide total external reflection to high energy radiation incident on the plates from a high energy radiation source, to focus the incident high energy radiation on a designated surface, wherein each plate has a thickness in the range of 50-70 µm; and

receiving the focused high energy radiation from the multi-foil optic onto a lithographic specimen via a lithographic mask.

- 7. (Original) The method of claim 6, wherein the high energy radiation comprises X-ray radiation.
- 8. (Original) The method of claim 6, wherein the high energy radiation comprises extreme ultraviolet (EUV) radiation.
  - 9. (Currently Amended) A high energy lithographic system, comprising: a high energy source;

a multi-foil optic for focusing high energy radiation from the high energy source, the multi-foil optic comprising a plurality of flat plates each having a reflecting surface, and positioned normal to an arc to provide total external reflection to high energy radiation incident on the plates from a high energy radiation source, to focus

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the incident high energy radiation on a designated surface, wherein each plate has a

thickness in the range of 50-70 µm; and

a mask, which receives focused high energy radiation from the multi-foil optic

and selectively blocks some of the radiation to form a pattern on a specimen that is

exposed to high energy radiation passing through said mask.

10. (Original) The high energy lithographic system of claim 9, wherein the

high energy radiation comprises X-ray radiation.

11. (Original) The high energy lithographic system of claim 9, wherein the

high energy radiation comprises extreme ultraviolet (EUV) radiation.

12. (New) The multi-foil optic of claim 1, further comprising a coating on

each of the flat plates.

13 (New) The multi-foil optic of claim 1, further comprising a multilayer

coating on each of the flat plates.

14. (New) The multi-foil optic of claim 1, wherein the multi-foil optic has a

size within a volume of about 5 mm<sup>3</sup>.

15. (New) The method of claim 6, wherein the multi-foil optic comprises a

coating on each of the flat plates.

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16 (New) The method of claim 6, wherein the multi-foil optic comprises a multilayer coating on each of the flat plates.

- 17. (New) The method of claim 6, wherein the multi-foil optic has a size within a volume of about 5 mm<sup>3</sup>.
- 18. (New) The high energy lithographic system of claim 9, wherein the multi-foil optic comprises a coating on each of the flat plates.
- 19 (New) The high energy lithographic system of claim 9, wherein the multi-foil optic comprises a multilayer coating on each of the flat plates.
- 20. (New) The high energy lithographic system of claim 9, wherein the multi-foil optic has a size within a volume of about 5 mm<sup>3</sup>.